cannot be produced in a single exposure process using devices and methods of the prior art.

It is very likely possible to produce 2.5D and 3D structures by repeated use of the known methods. Thus, it would be possible to apply a first layer on a substrate, to expose and then to develop the latter after positioning of the image, wherein the substrate is chemically solidified or dissolved depending on the exposure and polarity of the lacquer, and to coat the substrate again with a further layer and to expose and develop the latter again. The steps can be repeated as often as desired, for a corresponding number of desired layers and therefore stacked layouts.

It is obvious that all the aforementioned process steps have to be carried out for the development of each layer, which leads to a very great outlay and therefore to high costs. Furthermore, the probability of errors for each possible type of error increases with each additional process step. In particular, the correct lateral position during the exposure is an error-sensitive step, which can lead to an accumulated loss of quality.

Embodiments of the present invention eliminate or significantly reduce the drawbacks of the prior art. In particular, embodiments of the present invention aim to carry out the exposure in a quicker and easier way and to reduce the errors of all kinds.

All combinations of at least two features given in the description, in the claims and/or the drawings also fall within the scope of the invention. In stated value ranges, values lying inside the stated limits are also deemed to be disclosed as limiting values and can be claimed in any combination.

A first aspect of the invention relates to a method for the exposure of a photosensitive coating, comprising at least a first photosensitive area and a second photosensitive area, wherein the first area reacts to photons of a first wavelength and the second area, in particular overlapping the first area, reacts to photons of a second wavelength, wherein the first wavelength is different from the second wavelength, wherein the method comprises the following steps, in particular in the following sequence:

- exposure of the coating to the photons of the first wavelength,
- exposure of the coating to the photons of the second wavelength,

wherein there is no focus of the photons on the photosensitive areas.

In the following text, the photosensitive areas are referred to merely as areas.

A second aspect of the invention further relates to a device for the exposure of a photosensitive coating, comprising at least a first photosensitive area and a second photosensitive area, wherein the first photosensitive area reacts to photons of a first wavelength and the second photosensitive area reacts to photons of a second wavelength, wherein the first wavelength is different from the second wavelength, comprising a radiation device for the exposure of the coating to the photons of the first wavelength and for the exposure of the coating to the photons of the second wavelength, wherein there is no focus of the photons on the photosensitive areas.

Embodiments of the invention further relate to an article, produced with the method according to the invention and/or the device according to the invention.

The essence of the invention consists in particular in the fact that individual focusing of the photons on the individual photosensitive area is not necessary, since both areas have been deposited typically in thin